

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 17979-034US1	Application No. 2005/562257
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Shafer et al.	
		Filing Date Herewith	Group Art Unit

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
WC	AA	US2003/174408	9/18/2003	Rostalski Hans-Juergen et al.			
↓	AB	US2005/024609	2/3/2005	De Smit et al.			
	AC	US2005/074704	4/7/2005	Endo et al.			
	AD	US2005/0179877	8/18/2005	Mulkens et al.			
	AE	US2005/0219707	10/6/2005	Schuster et al.			

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
WC	AF	WO2005/006026	1/20/2005	WIPO				
↓	AG	WO2005/081067	9/1/2005	WIPO				
	AH	EP0291596B1	1/19/1994	EPO				
	AI	WO2005/059645	6/30/2005	WIPO				
	AJ	WO2005/059618	6/30/2005	WIPO				
	AK	WO2004/019128	3/4/2004	WIPO				
	AL	WO2005/031823	4/7/2005	WIPO				

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
WC	AM	Hoffnagle, J.A. et al. "Liquid immersion deep-ultraviolet interferometric lithography", Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena, American Vacuum Society, New York, NY, US, vol. 17, no. 6, November 1999 (1999-11), pages 3306-3309
↓	AN	Smith, et al. "Water-based 193nm immersion lithography", online, 28 January 2004, retrieved from the internet: URL:http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20RIT%20microstepper%20efforts%20Smith.pdf , retrieved on 2005-05-24
	AO	
	AP	

Examiner Signature /William Choi/	Date Considered 02/23/2007
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	